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RESPONSE UNDER 37 CFR 1.116  
EXPEDITED PROCEDURE  
EXAMINING GROUP 1711

PATENT  
Attorney Docket No. 203924

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

Kodama et al.

Application No. 09/502,834

Filed: February 11, 2000

For: POLYBENZAZOLE ARTICLE  
AND PRODUCTION METHOD  
THEREOF

Art Unit: 1711

Examiner: D. Truong

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**PENDING CLAIMS AFTER AMENDMENTS MADE IN  
RESPONSE TO OFFICE ACTION DATED FEBRUARY 20, 2002**

1. A polybenzazole article superior in light resistance, which comprises a polybenzazole and a light-resisting agent that allows for a regular reflectance of the article of not more than 30% in not less than 30% of the wavelength region of from 450 nm to 700 nm, wherein the light-resisting agent is at least one member selected from the group consisting of aniline, *o*-phenylenediamine, *m*-phenylenediamine, *p*-phenylenediamine, *o*-aminophenol, *m*-aminophenol, *p*-aminophenol, 2-amino-4-nitrophenol, 2-amino-4-sulfonamide, and 1,8-diaminonaphthalene.

2. The polybenzazole article of claim 1, wherein the light-resisting agent allows for a regular reflectance of the article of not more than 20% in not less than 10% of the wavelength region of from 450 nm to 700 nm.

3. The polybenzazole article of claim 1, which has a strength of not less than 35 g/d.

6. The polybenzazole article of claim 1, wherein the light-resisting agent is contained in a proportion of 0.01 to 20% by weight of the article.